



The Fine Line: Autumn 2017 Videos for the eBeam Community

Shot Talk: A Word from Our Sponsor

Aki Fujimura, CEO of D2S, provides his takeaways from the latest eBeam Initiative surveys and the recently concluded SPIE Photomask Technology Conference, and updates on the latest D2S developments in EUV and GPU acceleration.



A Japanese version of the video can be found [here](#). Leo Pang, chief product officer of D2S, also recaps these developments in [Chinese](#).



Tech Talk

Tom Faure of GLOBALFOUNDRIES explains what's new and different with EUV masks--including new performance and design requirements that are driving the need for multi-beam mask writing; new material, equipment and data challenges; and changes to mask data infrastructure and processing.



Video Archive

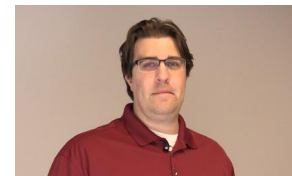
The Fine Line: Summer 2017 Edition



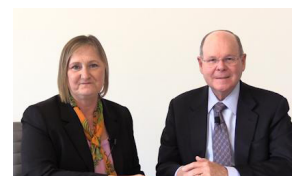
[Shot Talk:](#)
[Aki Fujimura, D2S](#)



[Shot Talk:](#)
[Leo Pang, D2S](#)



[Tech Talk:](#)
[Ryan Pearman, D2S](#)



[Perspectives:](#)
[Jim Wiley, SPIE BACUS](#)

Perspectives

Jed Rankin of GLOBALFOUNDRIES and co-chair of next year's SPIE Photomask Technology Symposium shares his predictions on the arrival of EUV for high-volume chip manufacturing, what he thinks about the progress with multibeam mask writing, and his take on three EUV mask issues that keep the industry up at night--rising data complexity, mask quality and inspection.



To unsubscribe, email requests@ebeam.org

[Click to view our entire video library](#)

The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please email requests@ebeam.org or visit www.ebeam.org